



1. Title:	Progress on the Realization of EUV Lithography
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3. Abstract body:

ASML is addressing the critical challenges of EUV Lithography, covering all key technology areas, including defect-free mask handling, reflective optics technology, contamination control, EUV source, and vacuum technology. We are realizing two pre-production exposure tools to minimize the risk, for early learning of using EUVL, and to support the development of the global infrastructure of masks, sources, and resist. These tools will be used in research centers by ASML, our co-developers, and our customers for process development, to prove out the promise of EUVL and to set the foundation for the commercialization of the technology.

In this presentation we will give a technical status overview, including an update on the integration and qualification of the Alpha tools, results on source investigations, handling reticles without adding particles, polishing results on the optics, and vacuum technology. We will also provide a status update on the readiness of EUVL for production.